



International Workshop on

Advanced Patterning Solutions

The 10th International Workshop on Advanced Patterning Solutions

第十届国际先进光刻技术研讨会

September 10-11, 2026, Shenzhen World, Shenzhen, Guangdong Province, China

2026 年 09 月 10 日至 11 日，深圳国际会展中心，广东深圳，中国

(September 09 for registration, 9 月 9 日注册)

Agenda 会议日程

Program Chairs:

Jiangliu Shi 师江柳, Chief Scientist, SAMT

Shisheng Xiong 熊诗圣, Professor, Zhangjiang Lab

Zongchang Yu 俞宗强, President, DJEL

Registration 注册		
09 Sep. 2026	14:00-17:00	Front of Mangrove A, Second Floor, South Lobby, Shenzhen World 深圳国际会展中心南登录大厅，2 层，红树林厅 A 前
10-11 Sep. 2026	08:00-17:00	
<u>DAY 1:</u>		
<u>10 Sep. 2026 (Thursday)</u>		
Mangrove A, Second Floor, South Lobby, Shenzhen World 深圳国际会展中心－南登录大厅，2 层，红树林厅 A		
<u>DAY 1-Morning</u>		
08:30-09:00	Opening Ceremony & Welcome Address Chair: Yayi Wei	
Welcome Address	Conference Chairs Address Host/Organizer Address	
09:00-10:10	Plenary Session I Chair: Shisheng Xiong (Zhangjiang Lab)	
	<i>5 minutes Q&A for each talk</i>	
09:00-09:35	Zongliang Huo (YMTC): (KEYNOTE) Scaling Up Vertically: How Photolithography and Metrology Drive 3D NAND Evolution	
09:35-10:10	Han Wang (The University of Hong Kong): (KEYNOTE) A Novel Nanomaterials Composite Pellicle for Advanced Lithography	
10:10-10:40	Group Photo & Coffee Break	
10:40-11:50	Plenary Session II Chair: Zongchang Yu (DJEL)	

	<i>5 minutes Q&A for each talk</i>
10:40-11:15	Nan Lin (Beihang University): (KEYNOTE) Next Generation of Laser Driven EUV source
11:15-11:50	Kris Leask (Mycronic AB): (KEYNOTE) A cost-effective registration metrology solution for binary and phase-shift photomasks
11:50-13:50	Poster Session Authors should be present at your poster.
12:00-13:00	Lunch
DAY 1-Afternoon	
13:50-15:40	Patterning Session Chairs: Jiangliu Shi (SAMT) & Yaobin Feng (YMTC)
	<i>5 minutes Q&A for each talk</i>
13:50-14:25	Qiang Wu (Fudan University): (KEYNOTE) Physical Mask, Photoresist, Lithography Model, and DICO
14:25-14:50	Wenzhang Li (Fujian Jinhua Integrated Circuit Co., Ltd): (INVITED) Etch Model application in SADP and Cut Processes: Contour simulation and PWQ Prediction
14:50-15:15	Yoshiaki Yamada (Cobetter): (INVITED) Metal Removal Filter Membranes with Acid Resistance for Lithography Chemical Applications
15:15-15:40	Si Wu (University of Science and Technology of China): (INVITED) Reversible photoresists for nanoimprint lithography
15:40-16:10	Coffee Break
16:10-17:50	AI + Lithography Session Chairs: Weimin Gao (Tsinghua Univ.) & Junwei Lu (CXMT)
	<i>5 minutes Q&A for each talk</i>
16:10-16:35	Ye Lu (Fudan University): (INVITED) How AI is going to help accelerate DTCO?
16:35-17:00	Yuzhe Ma (The Hong Kong University of Science and Technology (Guangzhou)): (INVITED) Robust, Manufacturable, and Curvilinear Optical Proximity Correction
17:00-17:25	Hao Geng (ShanghaiTech University): (INVITED) Paradigm Shift in AI-Driven Semiconductor Manufacturing: Point Tool, Foundation Model, and Agent
17:25-17:50	Le Hong (Siemens): (INVITED) Advanced ML/AI design-technology co-optimization (DTCO) accelerates process node development ramp-up.

18:30-18:35	Best Poster Award 最佳墙报颁奖 Mangrove C, Second Floor, South Lobby, Shenzhen World 深圳国际会展中心—南登录大厅，2层，红树林厅 C
18:35-20:00	Welcome Banquet for all attendees 晚宴 Mangrove C, Second Floor, South Lobby, Shenzhen World 深圳国际会展中心—南登录大厅，2层，红树林厅 C

Day 2: 11 Sep. 2026 (Friday) — Parallel Session I, 并行报告会场 I Hall 5, 2nd Floor, South Lobby, Shenzhen World 深圳国际会展中心—南登录大厅，2层5号会议室	
DAY 2-Morning	
08:30-10:05	Equipment Session Chairs: Kaidong Xu (Leuven Instruments) & Yun Zhan (XMC) <i>5 minutes Q&A for each talk</i>
08:30-08:55	Taiyen Peng (Leuven Instruments): (INVITED) Optimizing photoresist line-width roughness via combined ICP and ion beam shaping process
08:55-09:20	Tianyuan Chen (SMEE): (INVITED) Research on Simulation Strategies for Decomposing CDU Error Terms in KrF Lithography Systems
09:20-09:45	Fang-fang Duan (ASML): (INVITED) High accuracy, high throughput large field XT260 designed for supporting 3DIC and silicon interposer roadmaps
09:45-10:05	Likun Dong (Lithography Equipment Manufacturing Technology Innovation Center): Research on Thermal Time-Constant Model and influencing Factors of Cooling Water for Motor Used in Semiconductor-Equipment
10:05-10:30	Coffee Break
10:30-12:05	Metrology and Inspection Session I Chairs: Nan Lin (Beihang University) & Liguang Zhang (SEIDA) <i>5 minutes Q&A for each talk</i>
10:30-10:55	Chih-Hung Hsieh (Siemens): (INVITED) Advancing Massive Metrology for Next-Generation Semiconductor Manufacturing
10:55-11:20	Oracle Shen (Carl Zeiss): (INVITED) Extended Portfolio and New Features for More Flexibility in Registration Measurement
11:20-11:45	Puja Kadkhoda (OPTEST GmbH): (INVITED) Precision measurement techniques for quality control of VUV optical components
11:45-12:05	Lijun Zhou (Zhejiang University): Wafer alignment using vortex-beam interferometry

12:05-13:30	Lunch
DAY 2-Afternoon	
13:30-14:55	Metrology and Inspection Session II Chairs: Dean Wu (YMTC) & Jin Li (KLA)
	<i>5 minutes Q&A for each talk</i>
13:30-13:55	Maohua Ren (United Semiconductor (Xiamen) Co., Ltd.): (INVITED) Preliminary study of focus-dependent process window assessment using Reticle Inspection Images
13:55-14:15	Huajun Zhang (Lithography Equipment Manufacturing Technology Innovation Center): Co-simulation technology of multi-axis heterodyne interferometer
14:15-14:35	Cheng Li (Hangzhou Institute for Advanced Study, UCAS): Transparent-Material-Compatible Hierarchical Alignment for Nanoimprint Lithography Using Diffraction-Enhanced Markers and Moiré Amplification
14:35-14:55	Yuhang He (Tsinghua University): LASSO-based Zernike-Legendre overlay decomposition
14:55-15:20	Coffee Break
15:20-16:45	Other Lithography Technology Session Chairs: Cuifang Kuang (Zhejiang University) & Jicheng Feng (ShanghaiTech University)
	<i>5 minutes Q&A for each talk</i>
15:20-15:45	Jicheng Feng (ShanghaiTech University): (INVITED) Atomic-level arrangement of matter into structural arrays
15:45-16:05	Ruobing Bai (Shanghai Jiao Tong University): DNA-directed assembly to complement EUV for sub-5 nm patterning
16:05-16:25	Haoyu Kan (Hangzhou Institute for Advanced Study, UCAS): Voltage-dependent pattern evolution and process window establishment in localized interface-heating ultrafast thermal nanoimprint lithography
16:25-16:45	Na Li (Shanghai University): Desk-scale EUV exposure system based on Xe-DPP source and talbot lithography for sub-100 nm photoresist patterning
16:45-16:50	Closing Plenary Address 闭幕致辞 Chairs: Shisheng Xiong (Zhangjiang Lab)

Day 2:	
11 Sep. 2026 (Friday) – – Parallel Session II, 并行报告会场 II	
Hall 6, 2nd Floor, South Lobby, Shenzhen World	
深圳国际会展中心—南登录大厅, 2层6号会议室	
DAY 2-Morning	
08:30-10:25	AI + Computational Lithography Session Chairs: Xu Ma (BIT) & Kan Zhou (Haina Institute of Engineering)

	<i>5 minutes Q&A for each talk</i>
08:30-08:55	Zizheng Cao (Zhejiang University): (INVITED) AI-Accelerated Computational Lithography: Toward Lightweight and Interpretable Mask Synthesis for Advanced Nodes
08:55-09:20	Shengrui Zhang (DJEL): (INVITED) AI-powered hotspot prediction for patterning from SEM contour: physics-hybrid and pure AI models
09:20-09:45	Shanqi Tao (AMEDAC): (INVITED) Automated lithography modeling workflow based on general-purpose agent architecture: from dedicated physical models to scalable AI agents
09:45-10:05	You Wu (Tsinghua University): Photoresist contour-supervised deep learning for ILT
10:05-10:25	Yu Feng (Fudan University): GNN-Guided Local Refinement for Efficient Layout Decomposition with DSA-MP
10:25-10:45	Coffee Break
10:45-12:10	AI + DTCO Session Chairs: Chen Shen (PFTN) & Xiaoming Liu (Empyrean Tech)
	<i>5 minutes Q&A for each talk</i>
10:45-11:10	Ningmu Zou (Nanjing University): (INVITED) DVCC-GNN: A dual-view cross-channel graph neural network for lithography hotspot detection
11:10-11:30	Caiwei Shang (Fudan University): AI-driven closed-loop simulation framework for DSA toward DTCO in logic chip manufacturing
11:30-11:50	Yuyang Liu (Nanjing University): CHROME: Contact hole robust optimization via multi-objective evolution
11:50-12:10	Fengyun Long (Guangdong University of Technology): DPFF-driven parametric curvilinear mask rule compliance
12:10-13:30	Lunch
DAY 2-Afternoon	
13:30-14:55	Computational Lithography Session Chairs: Jing Li (Zhejiang Univeristy) & Feng Shao (Siemens)
	<i>5 minutes Q&A for each talk</i>
13:30-13:55	Jie Liu (ASML-Cymer): (INVITED) Convolved Bandwidth (CBW): A New Laser Bandwidth Metric for Improved CD Matching and EPE Reduction
13:55-14:15	Minhao Wu (NICIC): A hyper-NA EUV SMO and hot spot removal study with 16 nm minimum pitch and low n and high k absorbers

14:15-14:35	Hanzhi Zhang (Changchun University of Science and Technology): The High-Efficiency EUV Mask Optimization Method Based on Pixelated Absorber Layer Correction
14:35-14:55	Rui Lian (Beijing Institute of Technology): Seed-guided parallel phase unwrapping with bucket sorting and overlapped sub-blocks
14:55-15:20	Coffee Break
15:20-17:05	Computational Lithography and Process Session Chairs: Sikun Li (SIOM) & Yijiang Shen (Guangdong University of Technology)
	<i>5 minutes Q&A for each talk</i>
15:20-15:45	Kobelkov Sergey (Huawei Technologies Ltd. & Lomonosov Moscow State University): (INVITED) Shot-Count Aware Inverse Lithography Technology via Geometric Regularization
15:45-16:05	Jinghong Liu (Beijing Superstring Academy of Memory Technology): Surface restoration mechanisms in 3D structure staircase fabrication: mitigating photoresist scumming and delamination on fluorinated poly-silicon trenches
16:05-16:25	Ignat Moskalenko (Huawei Technologies Ltd.): New approach for OPC model self-consistency improvement
16:25-16:45	Haofeng Guo (Changchun Institute of Optics, Fine Mechanics and Physics, CAS): A Boundary-Iterative Hybrid Method Combining Runge-Kutta BPM and Multilayer Transfer Matrices for Mask Imaging
16:45-17:05	Yuxiang Yin (ShanghaiTech University): Electric Proximity Correction for Faraday Lithography
17:05-17:10	Closing Plenary Address 闭幕致辞 Chairs: Zongchang Yu (DJEL)

<u>Day 2:</u> <u>11 Sep. 2026 (Friday) – – Parallel Session III, 并行报告会场 III</u> Hall 9, 2nd Floor, South Lobby, Shenzhen World 深圳国际会展中心—南登录大厅, 2层9号会议室	
<u>DAY 2–Morning</u>	
08:30-10:10	Photoresist Session Chairs: Guoqiang Yang (ICCAS) & Xudong Guo (ICCAS)
	<i>5 minutes Q&A for each talk</i>
08:30-08:55	Ming-Qiang Zhu (Huazhong University of Science and Technology): (INVITED) Multi-tone photopatterning via photoacid-induced crosslinking/ degradation of poly(2,3-dihydrofuran)

08:55-09:20	Hideaki Tsubaki (Fujifilm Corporation): (INVITED) Reconsidering the role of fluorinated materials in advanced ArF immersion resists: Toward fluorine-free material design
09:20-09:45	Huie Zhu (Zhangjiang Lab): (INVITED) AI-Driven pKa Prediction of Photoacid Generators
09:45-10:10	Victor Sumerin (Pibond): (INVITED) High-temperature, gap filling, planarizing SOC materials for advanced ArF and EUV processes
10:10-10:40	Coffee Break
10:40-12:15	X-Ray for Lithography Session Chairs: Xiaosong Liu (USTC) & Guangcai Chang (IHEPCAS) <i>5 minutes Q&A for each talk</i>
10:40-11:05	Zhao Wu (National Synchrotron Radiation Laboratory, University of Science and Technology of China,): (INVITED) Recent researches on extreme ultraviolet lithography at the Hefei light source
11:05-11:30	Zirui Gao (Institute of High Energy Physics, CAS): (INVITED) Nano-resolution nondestructive 3D imaging capabilities of microchips at the HEPS ID19 beamline
11:30-11:55	Peng Li (National Synchrotron Radiation Laboratory, University of Science and Technology of China): (INVITED) A coherent lensless microscope for EUV mask inspection at Hefei Light Source
11:55-12:15	Yike Chen (Shanghai Synchrotron Radiation Facility and East China University of Science and Technology): Laser-assisted post-exposure baking for maskless grayscale lithography based on photoacid diffusion control
12:15-13:30	Lunch
DAY 2-Afternoon	
13:30-15:10	Mask Session I Chairs: Modern Xu (Carl Zeiss) & David H. Wei (GDUT) <i>5 minutes Q&A for each talk</i>
13:30-13:55	Sebastian Vollmar (Carl Zeiss SMT GmbH): (INVITED) Overcoming throughput and capability limits in photomask repair: a roadmap perspective
13:55-14:20	Hongyan Yang (SUSS MicroTec (Shanghai) Co., Ltd): (INVITED) Develop Process: Hardware Solutions
14:20-14:45	Jie Liu (Hunan University): (INVITED) A Scalable Model-Based Curvilinear Mask Fracturing Method with Overlapping Shots
14:45-15:10	Jingwei Chen (Mycronic (Shanghai) Co., Ltd.):

	(INVITED) Extending mature node mask manufacturing beyond EOL tools
15:10-15:30	Coffee Break
15:30-17:00	Mask Session II Chair: Lifeng Duan (Yuweitek) & Jie Liu (Hunan University)
	<i>5 minutes Q&A for each talk</i>
15:30-15:55	Zhengzhou Tian (New Ray Mask Technology Corporation): (INVITED) Production Qualification of a New Optical Photomask Inspection Platform for Mature-Node Reticle Quality Control
15:55-16:20	Xijun Li (Zhejiang Fuxi Opto-electronic Manufacturing Co., Ltd.): (INVITED) Hybrid photomask and wafer direct imaging using a DUV mask writer
16:20-16:40	Li Liu (Huazhong University of Science and Technology): Pushing the Resolution Limit of Coherent Diffractive Imaging
16:40-17:00	Yatian Zhang (Beijing Institute of Technology): Adaptive grid expansion for single-shear fourier wavefront reconstruction in lateral shearing interferometry
17:00-17:05	Closing Plenary Address 闭幕致辞 Chairs: Jiangliu Shi (SAMT)

Agenda is subject to change

Poster Session**10 Sep. 2026****11:50-13:50 Outdoor of Mangrove A 红树林厅前廊**

Poster-007	Junqi Yang* , Rui Xu, Jiaqi Liu, Chenxing Dong, Chuan Zhang (Zhangjiang Laboratory) Efficient inverse lithography technology based on a self-supervised swinIR model
Poster-011	Shiyang Li , Linzi Wu, Bojian Wu, Hengbo Li, Xiaolei Wen, Keqiang Qiu*, Zhao Wu, Yilin Hong (National Synchrotron Radiation Laboratory, University of Science and Technology of China) Achromatic Talbot lithography with Au transmission gratings achieves 20 nm half-pitch resolution
Poster-017	Wei Zhu ^{1,*} , Sheng Huang ¹ , Allen Wu ¹ , Bin Zou ² , Haotian Zhu ² , Liying Jiang ² (¹ Nexchip Semiconductor Corporation; ² Shanghai Yuwei Semiconductor Technology Corporation) A systematic investigation of mark design in advanced lithography
Poster-030	Ankita Agarwal ¹ , Rachit Sharma ¹ , Ingo Bork ² , Vineeth Muralidharan ¹ , Manachala Sneith Reddy ¹ , Ranganadh Peesapati ¹ (¹ Siemens Digital Industries Software, Nalapad Brigade Centre; ² Siemens Digital Industries Software, Santa Clara) EPE aware shot placement for fracture of AR/VR photomasks
Poster-031	Zilang Wu ¹ , Yizhen Song ² , Weixuan Zeng ² , Xin Zhang ^{2,*} , Shisheng Xiong ^{1,2,*} (¹ Fudan University; ² Zhangjiang Laboratory) Explaining and resolving thickness dependence of microdomain orientation by extensive simulation of directed self-assembly
Poster-033	Wang Kang * , Lv Pan, Luo Zhaolong (Nexchip Semiconductor Corporation) ML-Driven Topography Bias Compensation in OPC for Enhanced Implant patterning
Poster-036	Amogh Raj ¹ , Rachit Sharma ¹ , Ranganadh Peesapati ¹ , Ingo Bork ² , Stephen Kim ² (¹ Siemens Digital Industries Software, Nalapad Brigade Centre; ² Siemens Digital Industries Software, Santa Clara) Printability-Aware MDP Verification for Curvilinear Masks Written with VSB Mask Writers
Poster-037	Caiwei Shang ^{1,2} , Chenran Zhang ^{1,2} , Donghao Han ^{1,2} , Rujie Cao ³ , Yan Zhang ² , Zili Li ¹ , Weixuan Zeng ^{2,*} , Shisheng Xiong ^{1*,2} (¹ Fudan University; ² Zhangjiang laboratory; ³ Shanghai Jiao Tong University) Simulation of overfilled Directed self-assembly contact holes for process window mapping from hole shrinkage to multiplication with compact model
Poster-038	Lin Sijun ^{1,2} , Wu Zhipeng ^{1,2,*} , Qi Yuejing ^{1,2,**} , Zhu Liling ^{1,2} , Lu Shiqing ^{1,2} , Zhou Xin ¹ (¹ Institute of Microelectronics of the Chinese Academy of Sciences; ² University of Chinese Academy of Sciences) Multi-scale Attention Enhanced ViT with Manual-feature-guided Gated Fusion for Wafer Defect Classification
Poster-041	Yin shiqi * , Wang kang, Luo zhaolong (Nexchip Semiconductor Corporation)

	Density-dependent sizing and MRC-free OPC solution for advanced-node lithography enhancement
Poster-042	Zhihao Zhao* , Haifeng Li [#] , Rui Ding, Weiqiang Xu, Yu Huang, Jianliang Lin, Jianhong Wu, Weichung Ma, Zhaolong Luo (<i>Nexchip Semiconductor Corporation</i>) Mechanism and Optimization of Electrostatic Adsorption-Induced Residue Defects in High-Density Photoresist Regions of Contact/Via Layers After Development
Poster-044	Hao Cheng^{1,*} , Wang Kang ¹ , Luo Zhaolong ¹ , Zhang Yihan ² , Hu Caoping ² (<i>¹Nexchip Semiconductor Corporation; ²Advanced Manufacturing EDA Co., Ltd</i>) Resource Allocation Optimization, Acceleration Characteristics, and Reliability Study of GPU-Accelerated Optical Proximity Correction
Poster-050	Yong Shi ^{1,*} , Caleb Wang ¹ , Chunhung Wu ¹ , Wenchun Huang (<i>AMEGADAC</i>) Reducing AF Missing in RBAF via Sub-Conflict Seed Retention
Poster-058	Cai Chen ¹ , Xiaodone Meng ^{1,2,*} , Hongbin Zhang ¹ , Jinhua Pei ¹ , Minchun Yang ¹ , Qi Zhang ¹ , Yebin Xu ¹ , Richard Zheng ¹ (<i>¹Advanced Manufacturing EDA Co., Ltd.; ²School of Integrated Circuits, Tsinghua University</i>) Improving OPC Simulation Accuracy via a Differentiable Additive Correction Framework
Poster-059	Jieyun Chen, Liang Xu* , Wenzhuang Liu, Yebin Xu, Qiang Yin, Haoming Guo, Richard Zheng (<i>AMEDAC</i>) High Sensitivity Contact Defect Detection based on Intra-FOV Average Contour
Poster-063	Fang Yin* , Zichen Yin, Pei Xie, Can Duan, Jazlyn Zhang (<i>STIC</i>) Optical mechanism analysis of photoresist peeling hotspots and detection in Optical Proximity Correction (OPC) verify
Poster-065	Shiyang Gao ¹ , Ningyuan Yang ² , Quanji Zhang ¹ , Shaowei Jin ¹ , Riqiang Huang ¹ , Xin Zhuang ^{1,*} , Xing Cheng ^{1,*} (<i>¹Department of Materials Science and Engineering, Southern University of Science and Technology; ²Department of Chemistry, Southern University of Science and Technology</i>) A New Type of Silicon-containing Epoxy Photoresist
Poster-066	Guowei Jiang, Di Liang, Ziqiang Liang, Xin Wei, Yaokun Li, Kaicong Liu (<i>Beijing Superstring Academy of Memory Technology</i>) Study of Multilayer Reticle Overlay Compensation
Poster-069	Jinjie Qu, Liang Xu* , Weizhu Ni, Qixin Xu, Haoming Guo, Jieyun Chen, Yi Lu (<i>AMEDAC SEBU DTCO</i>) High-efficiency AI SEM contour extraction for hotspot detection
Poster-073	Yihao Wu ¹ , Xinliang Li ² , Shisheng Xiong ^{1,2,*} (<i>¹Fudan University; ²Zhangjiang laboratory</i>) Accelerating defect inspection of Directed Self-Assembly with defect-aware image translation
Poster-074	Kaisheng Chen (<i>SemiMask Corp.</i>) Modeling the optical proximity effect in annular aperture imaging

Poster-077	Jiaming Gao , Shane Xu , Shuang Li (<i>Technology Development Dept. of Lithography, SiEn Co., Ltd.</i>) Enhancing Overlay Control and Thermal Management Strategies for DUV Reticles with Small Field
Poster-078	Kuizhi Xiao, Tao Zhu, Qin Li, Chenyang Ding (<i>Fudan University</i>) Segmented and Stitchable Fourth-Order Trajectory Planning for Fast Turn-Around Scanning in Lithography Stages
Poster-085	Jingjing Fan, Chong Wang, Haoxin Zuo, Fu Li, Yujin Jia, Shuoyu Xia, Yaokun Li, Qingchen Cao* , Jiangliu Shi (<i>Beijing Superstring Academy of Memory Technology</i>) ILT-Guided SRAF generation for optimizing lithography pattern performance
Poster-088	Yu Feng¹, Liyi Zhou¹, Haoyu Wang¹, Yiming Xu¹, Xinliang Li², and Shisheng Xiong^{1,2} (<i>¹Fudan University, China; ²Zhangjiang Laboratory</i>) Advancing Manufacturability in DSA-Aware Layout Decomposition through Reinforcement Learning
Poster-090	Xiaochen Zhou, Ganlin Song, Xinli Zhou, Jiahao Xi, Jinghong Liu, Mingyi Yao, Miao Jiang* , Jiangliu Shi (<i>Beijing Superstring Academy of Memory Technology</i>) Research on Imaging Quality near the Resolution Limit in Deep Ultraviolet Lithography
Poster-092	Hailong Zhu* , Amigo Li, Steven Luo, Allen Wu, Yong Li, Deming Dong (<i>Nexchip Semiconductor Corporation</i>) Research on the advanced lithography materials by optimizing dark-field defect inspection
Poster-095	Kaining Zhang^{1,2}, Lijun Zhou^{1,2}, Li Chen³, Jinming Gao^{1,2}, Xuan Zhuo^{1,2}, Peng Feng³, Zhongliang Li^{3,*}, Dong Liu^{1,2,*}, Xiangzhao Wang^{1,2,3*} (<i>¹Zhejiang University, 310027; ²ZJU-Hangzhou Global Scientific and Technological Innovation Center; ³Shanghai Institute of Optics and Fine Mechanics, Chinese Academy of Sciences</i>) A Lithography Alignment Measurement System Based on Sinusoidal Phase Modulation of Vortex Beams
Poster-096	Liao Wen Chao, Cui Jia Hao, Han Chun Chieh* (<i>LONGTU MASK TECHNOLOGY CO., LTD</i>) The Thermal Effect Prevention by Multi-Pass Printing
Poster-101	Yufan Lin ¹, Yingxiong Guo ¹, Yanbin Gong ², Shengrui Zhang ², C.M. Hu ², T.H. Ying ¹,Wenzhang Li ^{1,*} (<i>¹Fujian Jinhua Integrated Circuit Co., Ltd; ²Dongfang Jingyuan Electron Co., Ltd.</i>) Etch model application in layer to layer check
Poster-103	Chen Xu ^{1,2}, Jianjun He ¹, Huie Zhu ^{1,2,*} (<i>¹ Shanghai University, Shanghai; ²Zhangjiang Laboratory</i>) Molecular weight and polydispersity effects on electron beam lithography performance of RAFT-mediated PMMA
Poster-104	Tatsi Iao ¹, Fengnien Tsai ¹, T.H.Ying ¹, Shengrui Zhang ², Xinchen You ², Yutong Wang ², Chenjin Wang ², Yanbin Gong ², C.M. Hu², Wenzhang Li^{1,*} (<i>¹ Fujian Jinhua Integrated Circuit Co., Ltd;</i>

	<i>²Dongfang Jingyuan Electron Co., Ltd.)</i> Unified Etch-OPC Modeling for Enhanced Target Fidelity
Poster-105	Hangle Guo¹, Fengnien Tsai¹, T.H.Ying¹, C.M.Hu², Yanbin Gong², Siqu Wang², Shengrui Zhang², Wenzhang Li^{1,*} (<i>¹ Fujian Jinhua Integrated Circuit Co., Ltd; ²Dongfang Jingyuan Electron Co., Ltd.)</i>) Defects detection through etching model
Poster-111	Shengsheng Sun [*], Hailin Wu, Xin Chen, Lin Jia (<i>Lithography Equipment Manufacturing Technology Innovation Center</i>) A Wiener Model-Based Dose Prediction Method for Optical Transient Effects in Lithography
Poster-112	Mia Hu [*], Hao Wu (Jieretech) Development of in-situ wireless temperature measurement for wafers with an accuracy better than 0.5mK
Poster-113	Ziqiang Liang, Di Liang, Yaokun Li, Kaicong Liu, Xin Wei, Jinghong Liu, Jiangliu Shi, Guowei Jiang[*] (<i>Beijing Superstring Academy of Memory Technology</i>) An automated DBO mark generation approach based on python
Poster-114	Dinghai Rui,^{1,2,3} Libin Zhang,^{1,2,3} Yajuan Su,^{1,2,3} Yi Tong,⁴ Yifan Wu,⁴ Shengsheng Sun,⁴ and Yayi Wei,^{1,2,3,*} (<i>¹IMECAS; ²UCAS; ³State Key Laboratory of Fabrication Technologies for Integrated Circuits; ⁴Lithography Equipment Manufacturing Technology Innovation Center</i>) Transient and steady-state exposure models of mask and their influence on overlay accuracy
Poster-115	Di Liang, Ziqiang Liang, Kaicong Liu, Yaokun Li, Xin Wei, Jinghong Liu, Jiangliu Shi, Guowei Jiang[*] (<i>Beijing Superstring Academy of Memory Technology</i>) Genetic Algorithm-Driven OVL Mark Placement Optimization for Multi-Layer Reticles Based on Maximum nMU Metric
Poster-123	Xiaotong Xu, Fang Yu, Shujing Lyu[*], Yue Lu (<i>East China Normal University</i>) SEM image editing with continuous exposure dose control for lithography process
Poster-128	KunTang ¹, Jie Liang ¹, Liming Sun ², Bangcheng Yan ², Min Zhong ^{2,*} (<i>¹School of Microelectronics, Shanghai University, China; ²Shanghai Integrated Circuit Research and Development Center Co., Ltd.)</i>) Design and comparison of tri-layer and quad-layer photoresist schemes for patterning phase-change memory cells under immersion ArF lithography
Poster-129	Yahui Jing, Zhen Wu, Haonan Wang[*] (<i>Lithography Equipment Manufacturing Technology Innovation Center</i>) An Evaluation Method for Image Plane Stability in Projection Exposure Systems
Poster-130	Ming Hao ¹, Pan Zeng ², Bingqian Ma ², Ran Ji ^{2,*}, Wanjiao Zhang ^{1,*} (<i>¹University of Chinese Academy of Sciences, Beijing, China, 100049; ²Qingdao Germanlitho Co., Ltd)</i>)

	Hierarchical digital resist deposition for localized thickness engineering in Nanoimprint Lithography
Poster-131	Yingshuai Liu, Tengfei Yan* (<i>Shanghai University</i>) Quantitative Determination of the Acid Quantum Yield of Nonionic Photoacid Generators Using ¹ H Nuclear Magnetic Resonance Spectroscopy
Poster-133	Xinwei Hou ^{1,2,3}, Libin Zhang ^{1,2,3}, Dinghai Rui ^{1,2,3}, Yajuan Su ^{1,2,3}, AND Yayi Wei ^{1,2,3,*} (<i>¹Institute of Microelectronics of Chinese Academy of Sciences; ² University of Chinese Academy of Sciences, Beijing; ³State Key Laboratory of Fabrication Technologies for Integrated Circuits</i>) Wafer heating effects on photoresist in-plane displacement in DUV lithography
Poster-134	Zhenhao Chen, Lin Du, Xinyuan Mei, Yuyang Bian* (<i>Shanghai University</i>) Mitigating over-engineering in spectroscopic OCD metrology: extracting macroscopic physical baselines via partial least squares
Poster-136	Miao He ^{1,2}, Zhiping Mou ³, Xian Zhou ², Runchun Zhang ³, Jishuo Yang ³, Dingcheng Zeng ^{2,*} (<i>¹Chongqing University, Chongqing; ²XLMEC; ³Siemens EDA,</i>) Contour Based Lithography Model Demonstrate Enhanced Generalizability and Prediction Accuracy
Poster-137	Xinyuan Mei, Zhenhao Chen, Lin Du, Xiuzhen Lu ,Yuyang Bian (<i>Shanghai University</i>) A Recipe-to-Profile Process Emulator via Token-Embedding-Based Multimodal Semantics for Advanced OCD Metrology Integration
Poster-142	Songmao Zhang*, Yifan Wu, Shengsheng Sun, Mengting Chen (<i>Lithography Equipment Manufacturing Technology Innovation Center</i>) Flow-optics Multi-physics coupling analysis of airflow-induced image degradation in high-precision optical imaging
Poster-144	Yujie Liu *, Xiaobing Cui, Wenhao Yang, Baojun Zhao, Shiwei Tian (<i>Lithography Equipment Manufacturing Technology Innovation Center</i>) A Study on the Influence of Nonlinear Stiffness of Air-Float Bearing on the Dynamic Characteristics of Active Balancing Mass Systems
Poster-146	Zhaoxuan Li*, Xin Chen, Shengsheng Sun, Jia Lin (<i>Lithography Equipment Manufacturing Technology Innovation Center</i>) Fast Algorithm for Hopkins Lithography Imaging Based on Equivalent Fourier Transformation and Frequency-Domain TCC Constraint
Poster-147	Tian-Qi Zhang, Jia-Hui Ji*, Jia-Bo Yang, Xiang-Peng Meng (<i>Lithography System Manufacturing Technology Innovation Center</i>) A Two-Stage Spatial-Domain Sharpness Evaluation and Autofocus Method for Mask Inspection
Poster-149	Jisong Lu*, Wei Wang, Weize Tian, Min Zhou, Zhe Wang (<i>Lithography System Manufacturing Technology Innovation Center</i>)

	Active vibration isolation system for lithography equipment based on quasi-zero stiffness aerostatic support and skyhook damping control
Poster-150	Xue Wang, Hanshen Xin* (Shanghai University) Cation-Engineered Polymer-Bound PAGs for EUV Lithography
Poster-153	Hao Ding*, He Wang (Lithography System Manufacturing Technology Innovation Center) Moving Mirror Selection for Aberration Compensation in Lithography Projection Optics Based on Sensitivity Matrix and SVD
Poster-154	John Song*, Yazhou Meng, Qi Zhang, Benjamin Shen, Ray Zhou, Chunhung Wu, Wenchun Huang (AMEDAC) A physics-informed neural network for speeding up optical proximity correction
Poster-161	Yu Zhang, Jiamin Liu*, Shiyuan Liu* (Huazhong University of Science and Technology) Fast EUV lithography imaging algorithm based on U-Net
Poster-162	Yifan Wu, Songmao Zhang, He Wang, Shengsheng Sun, Shengwang Tan, Yonggang Wang (Lithography Equipment Manufacturing Technology Innovation Center) Modeling and Simulation of Objective Imaging Thermal Sensitivity Based on Opto-Mechanical-Thermal Multi-Field Coupling
Poster-163	Zheheng Liu*, Tianjuan Yang*, Langfeng Wen, Yanzhong Ma (Skyverse Tech. Co. Ltd) A Model-Free Method for Estimating 2D Tilt Angles of High-Aspect-Ratio 2D Periodic Nanostructures from CDSAXS Spectral Second Moments
Poster-165	Mengning Zhang, Yunzhi Zhang, Jianqiang Yao, Qin Li* (College of Intelligent Robotics and Advanced Manufacturing, Fudan University) Design of an externally preloaded piezoelectric compliant platform for large-load applications
Poster-166	Yihan Zhao^{1,2,3,*}, Lisong Dong^{1,2,3,*}, Jinyuan Tan^{1,2,3}, Yixuan Zou^{1,2,3}, Yayi Wei^{1,2,3,*} (¹EDA Center, Institute of Microelectronics of Chinese Academy of Sciences; ²University of Chinese Academy of Science; ³Key Laboratory of Fabrication Technologies for Integrated Circuits) A fast latent image simulation method for DUV lithography with underlying structures based on physics-informed neural networks
Poster-167	Jingchong Xu*, Yi Tong, Sa Wang, Wanzhen Song, Jiteng Yang (Manufacturing Technology Innovation Center) Lithography Scanner System Overlay Design Based on Budgeting and Dual-Engine Simulation
Poster-169	Fen Xue¹, Xin Shang¹, Long Xu¹, ShiZhi Lv², Li Ling², Yi Chen^{2,*} (¹Maskshop, Shanghai Integrated Circuit Equipment & Materials Industry Innovation Center; ²Mask Application Division, Advanced Manufacturing EDA Co., Ltd) A Method Based on Multiple Correction Parameters for Predicting Global CD Uniformity of Photomasks
Poster-170	Meiyu Zhang*, Binyi Ma, Yunlei Li, Changchang Jia, Zhanbiao

	Huangfu, Chen Guo (<i>Lithography Equipment Manufacturing Technology Innovation Center</i>) Research on Pattern Decomposition and Layout Co-Optimization for DOF-Robust KrF Lithography
Poster-176	HH Tang^{*1}, Chen Darin², Feng Li¹, Amigo Li¹, Steven Luo¹, Allen Wu¹, Yang Fei² (<i>¹Nexchip Semiconductor Corp.; ²KLA Corporation</i>) Optical CD enhancement: coupling effects of ion doping implantation and surface strained-layer thickness
Poster-182	Xueyi Luo[†], Zimu Li[†], Xiaorong Weng[†], Yuhua Li, Yifan Shen, Huanhua Wang, Xin Chen[*], Feipeng Yang[*] (<i>Suzhou National Laboratory</i>) Machine Learning-Assisted Prediction and Optimization of Photoresist Lithographic Performance via WAXS/GIWAXS Structural Fingerprinting
Poster-183	Ruizhe Yan, Tengfei Yan[*] (<i>Shanghai University</i>) Dual-method characterization and comparative analysis based on photoacid diffusion in chemically amplified resists
Poster-185	Meng Jin^{1,2}, Huie Zhu^{1,2*} (<i>¹School of Microelectronics, Shanghai University; ²Zhangjiang Laboratory</i>) Stripping of metal-containing photoresists by wet pretreatment assisted Cl ₂ /N ₂ plasma
Poster-186	Xiangyu Ma[*], Chao Chen, Langfeng Wen, Yanzhong Ma (<i>Skyverse Tech. Co. Ltd</i>) Research on In-line Ellipsometric OCD Metrology for High-Depolarization Ultra-Thick 3D NAND Films
Poster-187	Jiahenan Liu^{1,2}, Junjie Sun³, Ming Hao^{1,2}, Cheng Li^{1,2}, Haoyu Kan^{1,2}, Bingqian Ma³, Ran Ji^{3,*}, Wanjiao Zhang^{1,2,*} (<i>¹Hangzhou Institute for Advanced Study, UCAS, Hangzhou, China, 310024; ²University of Chinese Academy of Sciences, Beijing, China, 100049; ³Qingdao Germanlitho Co., Ltd</i>) Panel-level nanoimprint lithography on 310 × 310 mm square substrates for scalable manufacturing of large-area optical components
Poster-188	Fuxun Chen¹, Yanan Bao^{1,3}, Dawei Gao^{1,3}, Kan Zhou^{1,*}, Guodong Zhou^{1,2,*} (<i>¹College of Integrated Circuits, Zhejiang University; ²ZJU-Hangzhou Global Scientific and Technological Innovation Center, Zhejiang University; ³Zhejiang ICsprout Semiconductor Co., Ltd</i>) Suppressing FEM Data Missing-Induced PWA Errors: Performance Verification of Stepwise Regression Method
Poster-189	Yanan Bao^{1,2}, Jianming Wu², Fei Lin², Meng Xi², Dawei Gao^{1, 2}, Guodong Zhou^{1,3*} (<i>¹College of Integrated Circuits, Zhejiang University; ²Zhejiang ICsprout Semiconductor Co., Ltd; ³ZJU-Hangzhou Global Scientific and Technological Innovation Center</i>) Reducing Rework Rate via Pre-Development and Progressive Spin-Drying in Photolithography Development
Poster-190	Rui Wen^{1*}, Chengyu Fang¹, Kejie Wang¹, Pingsen Huang², Lingyi Guo², Gaolin Mu², Kevin Huang², Jincheng Pei² (<i>¹Chongqing</i>

	<i>Xinlian Microelectronics Co., Ltd.;² KLA Corporation</i> Customized Overlay Mark Design and Recipe Optimization for Addressing Metrology Challenges
Poster-192	<i>LIANG Tong, LI Jing* (Zhejiang University)</i> A Study on Refractive Index Variation Caused by Regional Airflow Disturbance along the Beam-Path for Precision Positioning
Poster-193	<i>PAN Zherui, LI Jing (Zhejiang University)</i> Test scheme and apparatus design for ultraviolet photodetector
Poster-195	<i>Huayong Wang*¹, Hang Fan, ¹ Biyu Ju¹, Lan Zhang², Faquan Liu², Haotian Lai², Kevin Huang², Jason Pei² (¹ Hua Hong Semiconductor (Wuxi) Limited; ² KLA Corporation)</i> A Novel Overlay Metrology Method for Flexible In-Die and Large-Mark Measurements

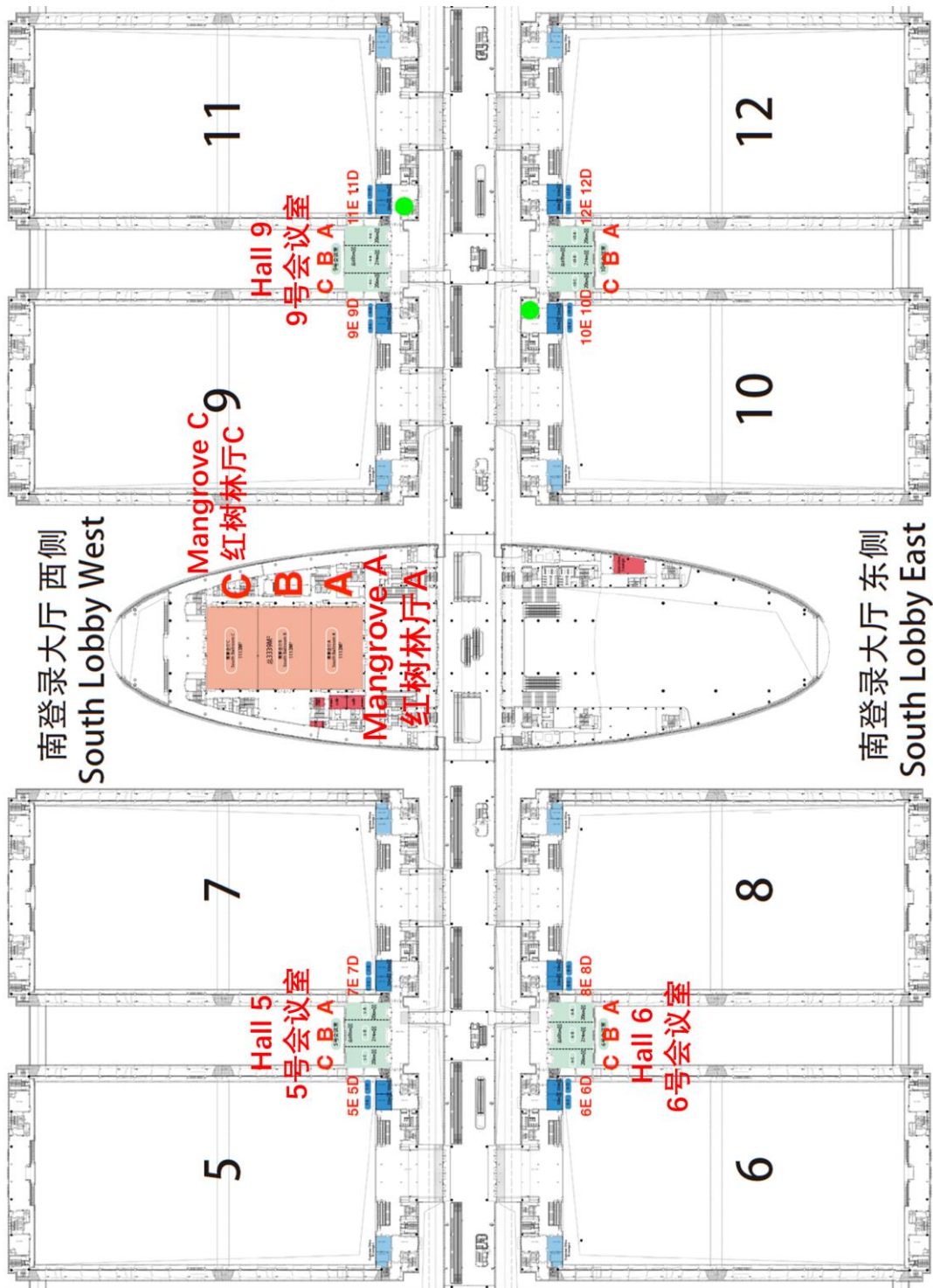
Agenda is subject to change

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Events

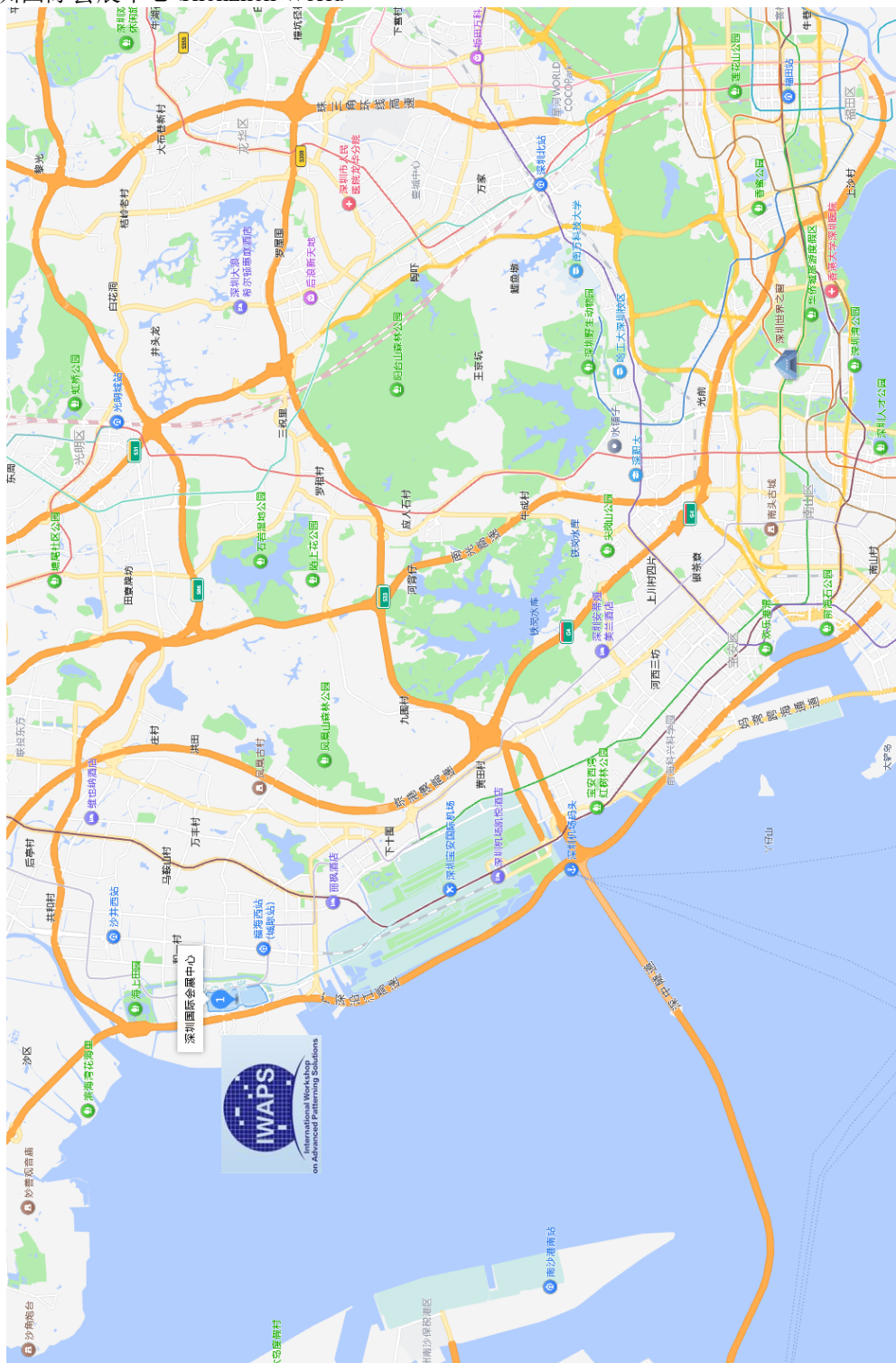
Item	Date	Time	Location
Registration	09 Sep.	14:00-17:00	Front of Mangrove A, Second Floor, South Lobby, Shenzhen World
	10-11 Sep.	08:00-17:00	深圳国际会展中心南登录大厅，2 层，红树林厅 A 前
Main Meeting	10 Sep.	08:30-18:00	Mangrove A, Second Floor, South Lobby, Shenzhen World 深圳国际会展中心南登录大厅，2 层，红树林厅 A
Parallel Meeting	11 Sep.	08:30-17:30	Hall 5/6/9, 2nd Floor, South Lobby, Shenzhen World 深圳国际会展中心南登录大厅，2 层 5 号 /6 号/9 号会议室
Poster Session	10 Sep.	11:50-13:50	Outdoor of Mangrove A 红树林厅 A 前廊
Group Photo	10 Sep.	10:10-10:40	South Lobby West (1 st Floor) 南登录大厅西侧门口（一层）
Banquet	10 Sep.	18:30-20:30	Mangrove C 红树林厅 C
Coffee Break	10-11 Sep.	10:10-10:50 14:50-16:00	Outdoor of Mangrove A 红树林厅 A 前廊
Lunch	10-11 Sep.	12:00-13:00	Mangrove C 红树林厅 C

南登录大厅二层主会场、分会场平面图



Locations

深圳国际会展中心 Shenzhen World





离馆出租车上客点
Departure Taxi Pick-up Point

主办方在南广场设置了出租车上车点,
运营时间:2026年9月9-10日
16:30-18:00

The organizer has set up the taxi
pick-up points at the South Plaza.
Operating Hours: 16:30 - 18:00,
September 9 - 10, 2026



馆间电瓶接驳车(1楼)
Free Shuttle Bus (L1)

地铁站 (12/120号线)
Metro Station

展馆门号
Gate No.

登录大厅对面-网约车(即停即走)
Ride-hailing



地面停车场
Parking Zones

1 4 9 14 16 地面停车场入口
Car Park Entrance Gate No.

地下停车场区域
Basement Parking Zones

P1 P2 P3 P4 P5 P8 P9 地下停车场入口
Basement Parking Entrance

请导航至深圳国际会展中心南
登录大厅东侧, 或地铁国展站